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PATENT
Customer No. 22,852
Attorney Docket No. 07553.0009

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
)
Michiaki SANO) Group Art Unit: 1765
)
Serial No.: 09/671,201) Examiner: L. Vinh
)
Filed: September 28, 2000)
)
For: PLASMA PROCESSING)
METHOD)

Assistant Commissioner for Patents
Washington, DC 20231

Sir:

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AMENDMENT

In reply to the Office Action dated January 9, 2002, the period for reply having been extended for one month by a request for extension and fee payment filed concurrently herewith, please amend the application as follows:

IN THE CLAIMS:

Please cancel claims 1-6 without prejudice or disclaimer, and add new claims 7-40, as follows:

7. (New) A plasma processing method for removing a photoresist film formed at a workpiece placed within a processing chamber, comprising:
- applying high-frequency power for biasing to the workpiece at a first power level;
 - raising the processing gas to a plasma; and

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